

Patent

Attorney's Docket No. 015290-440

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of )

Rajinder Dhindsa et al. )

Group Art Unit: 2813

Application No.: 09/689,845 )

Examiner: K. Christianson

Filed: October 13, 2000 )

For: STEPPED UPPER ELECTRODE  
FOR PLASMA PROCESSING  
UNIFORMITY )I hereby certify that this correspondence is being sent  
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Commissioner For Patents, Washington, D.C. 20231  
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SUPPLEMENTAL AMENDMENT  
(Printed name of person signing the  
certificate)Assistant Commissioner for Patents  
Washington, D.C. 20231

Sign: Laura Blair

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Sir:

Date: 1/17/02

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Further to the Amendment filed December 18, 2001, please amend the application  
as follows.

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**IN THE CLAIMS:**

TECHNOLOGY CENTER 2800

Please cancel Claims 13 and 20 without prejudice or disclaimer of the subject matter  
thereof and replace Claims 12 and 19 as follows:12. (Amended) A method of treating a semiconductor substrate in a plasma chamber,  
said method comprising the steps of:

supporting the semiconductor substrate on a bottom electrode;

supplying process gas to the chamber;

forming a plasma adjacent an exposed surface of an upper electrode; and

processing the semiconductor substrate with the plasma;